

Claims

What is claimed is:

1. A memory device comprising:
 - a first electrode;
 - a functional media formed over the first electrode, a state of the functional media changes based on a migration of electrons or holes when subject to an external electric field or light radiation, the state indicative of information content; and
 - a second electrode formed over the functional media.
2. The memory device of claim 1, wherein the functional media comprises at least one of an active layer and a passive layer.
3. The memory device of claim 1, wherein the first electrode or the second electrode comprises at least one selected from the group of tungsten, silver, copper, titanium, chromium, germanium, gold, aluminum, magnesium, manganese, indium, iron, nickel, palladium, platinum, zinc, alloys thereof, indium-tin oxide, conductive oxides, polysilicon, doped amorphous silicon, metal silicides, and various copper composition alloys.
4. The memory device of claim 1, wherein the first electrode or the second electrode comprise at least one selected from the group of conducting polymers, semi-conducting polymers, PEDOT/PSS, polyaniline, polythiethene material, doped conducting organic polymers, doped semiconducting organic polymers, undoped conducting organic polymers, undoped semiconducting organic polymers, oligomers, monomers, conducting metal oxides, conducting metal nitrides, conducting metal silicides, semiconducting metal oxides, semiconducting metal nitrides, semiconducting metal silicides, and conductive organic polymers.
5. The memory device of claim 1, wherein the first electrode or the second electrode comprise amorphous carbon.

6. The memory device of claim 1, wherein the first electrode or the second electrode comprise at least one of optically transparent oxide and sulfide material.

7. The memory device of claim 2, wherein the active layer comprises at least one of an organic, metal organic, and non organic material.

8. The memory device of claim 2, wherein the active layer comprises at least one selected from the group of polydiphenylacetylene, poly(t-butyl)diphenylacetylene, poly(trifluoromethyl)diphenylacetylene, polybis-trifluoromethyl)acetylene, polybis(t-butylidiphenyl)acetylene, poly(trimethylsilyl) diphenylacetylene, poly(carbazole)diphenylacetylene, polydiacetylene, polyphenylacetylene, polypyridineacetylene, polymethoxyphenylacetylene, polymethylphenylacetylene, poly(t-butyl)phenylacetylene, polynitro-phenylacetylene, poly(trifluoromethyl) phenylacetylene, poly(trimethylsilyl)pheylacetylene, polydipyrrylmethane, polyindoquinone, polydihydroxyindole, polytrihydroxyindole, furane-polydihydroxyindole, polyindoquinone-2- carboxyl, polyindoquinone monohydrate, polybenzobisthiazole, and poly(p-phenylene sulfide).

9. The memory device of claim 2, wherein the active layer comprises at least one of: materials of a nitro group, materials of an amino group, cyclopentadienyl, dithiolane, metilcyclopentadienyl, fulvalenediyl, indenyl, fluorenyl, cyclobis(paraquat-p-phenylene), bipyridinium, phenothiazine, diazapyrrenium, benzonitrile, benzonate, benzamide, carbazole, dibenzothiophene, nitrobenzene, aminobenzenesulfonate, and amonobenzanate.

10. The memory device of claim 2, wherein the active layer comprises molecular units with redox-active metals.

11. The memory device of claim 10, wherein the redox active metals comprise at least one of metallocenes complex and polypyridine metal complex.

12. The memory device of claim 2, wherein the active layer comprises at least one selected from the group of polyaniline, polythiophene, polypyrrole, polysilane, polystyrene, polyfuran, polyindole, polyazulene, polyphenylene, polypyridine, polybipyridine, polyphthalocyanine, polysexithiosene, poly(siliconoxohemiporphyrazine), poly(germaniumoxohemiporphyrazine), and poly(ethylenedioxythiophene).

13. The memory device of claim 2, wherein active layer comprises at least one selected from the group of aromatic hydrocarbons; organic molecules with donor and acceptor properties, metallo-organic complexes; porphyrin, phthalocyanine, and hexadecafluoro phthalocyanine.

14. The memory device of claim 13, wherein the organic molecules with donor acceptor properties comprises at least one selected from the group of N-Ethylcarbazole, tetrathiotetracene, tetrathiofulvalene, tetracyanoquinodimethane, tetracyanoethylene, cloranol, and dinitro-n phenyl.

15. The memory device of claim 13, wherein the metallo-organic complexes are selected from the group of bisdiphenylglyoxime, bisorthophenylenediimine, and tetraaza-tetramethylannulene.

16. The memory device of claim 2, wherein the active layer comprises organic material selected from the group comprising of polyacetylene, polyphenylacetylene, polydiphenylacetylene, polyaniline, poly(p-phenylene vinylene), polythiophene, polyporphyrins, porphyrinic macrocycles, thiol derivatized polyporphyrins, polymetallocenes, polyferrocenes, polyphthalocyanines, polyvinylenes, and polystyroles.

17. The memory device of claim 2, wherein the active layer comprises material selected from the group comprising of electric dipole elements, polymer ferroelectrics clusters, non-organic ferro-electrics, salts, alkalis, acids, and water molecules.

18. The memory device of claim 2, wherein the active layer comprises material that can dissociate in at least one of an electrical field and under light radiation.

19. The memory device of claim 18, wherein the material that can dissociate on anions that are selected from the group consisting of I, Br, Cl, F, ClO₄, AlCl₄, PF₆, AsF₆, AsF₄, SO₃CF₃, BF₄, BCl₄, NO₃, POF₄, CN, SiF₃, SiF₆, SO₄, CH₃CO₂, C₆H₅CO₂, CH₃C₆H₄SO₃, CF₃SO₃, N(SO₃CF₃)₂, N(CF₃SO₂)(C₄F₉SO₂), N(C₄F₉SO₂)₂, alkylphosphate, organoborate, bis-(4-nitrophenil) sulfonilimide, and poly(styrene sulfonate)(polyanions).

20. The memory device of claim 18, wherein the material that can dissociate on cations that are selected from the group consisting of Li, Na, K, Rb, Cs, Ag, Ca, Mg, Zn, Fe, Cu, H, and NH₄.

21. The memory device of claim 1, wherein the functional media comprises porous dielectric material.

22. The memory device of claim 21, wherein the porous dielectric material is selected from the group consisting of Si, amorphous Si, silicon dioxide (SiO₂), aluminum oxide (Al₂O₃), copper oxide (Cu₂O), titanium dioxide (TiO₂), boron nitride (BN), vanadium oxide (V₂O₃), carbon tri-nitride (CN₃), ferroelectric materials and barium-strontium titanate ((Ba, Sr) TiO₃).

23. The memory device of claim 1, thicknesses of the first electrode and the second electrode being at least about 0.01 μm or at most about 10 μm.

24. The device of claim 2, the active layer having a thickness of at least about 0.001 μm or at most about 5 μm.

25. The device of claim 2, a thickness of the active layer is about 10 to about 500 times greater than a thickness of the passive layer.

26. A method of fabricating an organic memory device that operates based upon electron-hole movement through a passive layer and an active layer, comprising:
forming a first electrode on a substrate;
forming the passive layer on the first electrode;
forming the active layer on the passive layer; and
forming a second electrode on the active layer.

27. The method of claim 26 further comprising forming the active layer *via* a chemical vapor deposition process.

28. The method of claim 26 further comprising forming the active layer *via* a gas phase reaction process.

29. The method of claim 26, further comprising forming the active layer formed *via* a spin coating process or a liquid phase reaction process.

30. The method of claim 26, further comprising applying a first voltage to the first non-copper electrode and the second electrode, to set an impedance state of the organic memory device, the impedance state representing information content.

31. The method of claim 26, further comprising applying a second voltage to the first electrode and the second electrode to determine an impedance state of the memory device, the impedance state representing information content.

32. A system that operates an organic memory device comprising:
means for changing an impedance state of the organic memory device; and

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means for containing information in the organic memory device based on the impedance state.